MPICORPORATION

READY FOR THE TEST™

MPI TS300 | 300 mm Manual Probe System

For accurate and reliable DC/CV and RF measurements

Microscope Mount and Movement

- Stable bridge for high quality optics
- Linear Z lift for easy reconfiguration
- 25 x 25 mm air bearing or 150 x 150 mm linear XY movement

Probe Platen

- Stable and rigid design
- Supports DC/CV and RF measurements
- Rectangular adjustments for RF positioners
- Designed for maximum thermal stability

Adjustable Platen Height

- Micrometer control for precise adjustment
- 20 mm range for various applications
- Including platen heigth reference scale

Unique Platen Lift

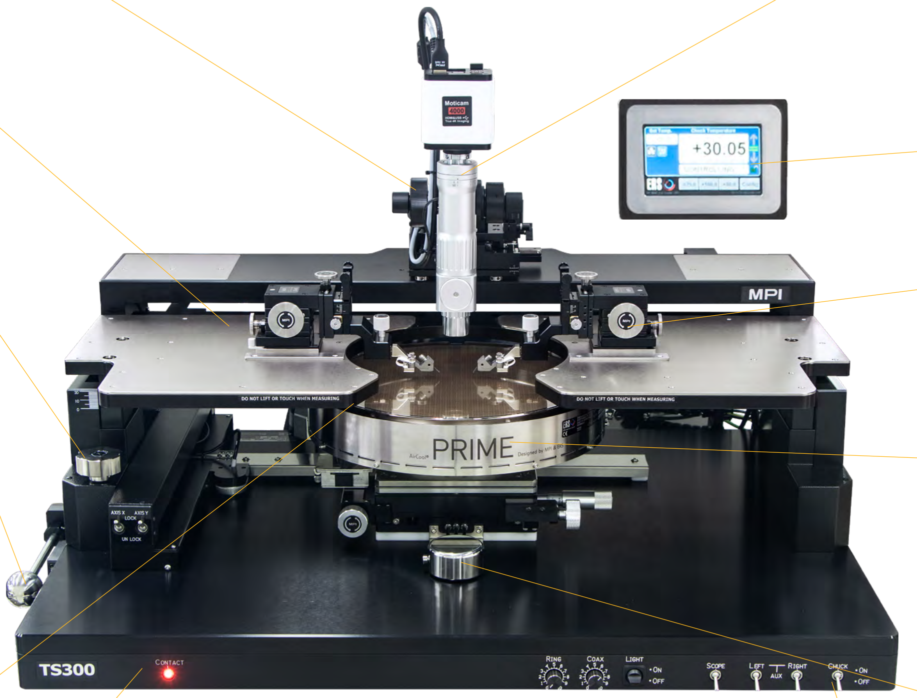
- Three discrete positions for contact, separation (300 µm) and safety loading 3 mm
- “Auto Contact“ position with ±1 µm repeatability for consistent contact quality
- Safety lock function at loading position

RF Calibration

- 2 auxiliary chucks for calibration substrates
- Built-in ceramic for accurate calibration
- 1 µm flatness for consistent contact quality

Small Footprint

- Designed for bench top use
- Comes with vibration absorber base
- Low profile design for maximum usability



Available Options

- Vibration isolation platform
- Vacuum pump and air compressor unit
- Probe card holder
- Table with integrated rack for thermal controller, computer and keyboard push tray (Dual monitor stand option & Instrument shelf option

Microscope and Optics Options

- Various optics options available
- Stereo MPI ST45 or single tube MPI SZ10, MZ12 with up to 12x zoom and 95 mm working distance
- High Power microscopes FS70/PSM-1000
- HDMI cameras, monitor user interface without computer

Thermal Chuck Integration

- Seamless integration of the thermal controller touch screen panel provides most convenient operation

DC and RF Positioners

- Supports up to 4 RF and 10 DC positioners
- Wide range of positioners available
- Dedicated probe arms for DC/CV and RF measurements

Modular Chucks

- Various non-thermal or thermal chucks
- Choice of triaxial or coaxial connection
- Wide range of temperature up to 300 °C
- Field upgradable for reduced cost of ownership
- Easy switch between center and small wafer size control

Chuck XY Stage Movement

- Unique puck controlled air bearing stage for quick single-handed operation
- 330 x 395 mm XY total stage movement
- 25 x 25 mm XY fine micrometer adjustment
- Resolution < 1.0 µm (0.04 mils) @ 500 µm/rev
- Extra wide Y-range for easy loading
- ±5° Theta fine adjustment

Front Mounted Vacuum Control

- Easy access
- Clearly marked

FACT SHEET - TS300, AST-AS-0085-01, 02-2025 © MPI 2025 Corporation - Data subject to change without further notice.